

| L Number | Hits | Search Text  | DB                             | Time stamp          |
|----------|------|--|--------------------------------|---------------------|
| 1        | 1514 | (wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:21 |
| 2        | 844  | ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:00 |
| 3        | 299  | ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)   | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:01 |
| 4        | 947  | (wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:56 |
| 5        | 537  | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)   | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:57 |
| 6        | 238  | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)) | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:23 |
| 7        | 180  | (wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam  | EPO; JPO                       | 2003/08/22<br>08:12 |
| 8        | 83   | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)   | EPO; JPO                       | 2003/08/22<br>08:11 |
| 9        | 171  | (airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)   | EPO; JPO                       | 2003/08/22<br>08:12 |
| 10       | 4    | ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) and (electron adj beam or ultraviolet)  | EPO; JPO                       | 2003/08/22<br>08:13 |

| L Number | Hits | Search Text  | DB                             | Time stamp          |
|----------|------|--|--------------------------------|---------------------|
| 1        | 1514 | (wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:21 |
| 2        | 844  | ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:00 |
| 3        | 299  | ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)   | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:01 |
| 4        | 947  | (wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:56 |
| 5        | 537  | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)   | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:57 |
| 6        | 238  | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)) | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>07:23 |
| 7        | 180  | (wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam  | EPO; JPO                       | 2003/08/22<br>08:19 |
| 8        | 83   | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)   | EPO; JPO                       | 2003/08/22<br>08:11 |
| 9        | 171  | (airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)   | EPO; JPO                       | 2003/08/22<br>08:41 |
| 10       | 4    | ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) and (electron adj beam or ultraviolet)  | EPO; JPO                       | 2003/08/22<br>08:13 |
| 11       | 1268 | (wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)   | EPO; JPO                       | 2003/08/22<br>08:44 |
| 12       | 349  | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)  | EPO; JPO                       | 2003/08/22<br>08:20 |
| 13       | 348  | ((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))  | EPO; JPO                       | 2003/08/22<br>08:21 |
| 14       | 0    | (airtight or hermetic\$5) and (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)))  | EPO; JPO                       | 2003/08/22<br>08:46 |

|    |       |  |                                |                     |
|----|-------|--|--------------------------------|---------------------|
| 15 | 46    | (evacuat\$3 or vacuum\$3) and (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)))  | EPO; JPO                       | 2003/08/22<br>08:28 |
| 16 | 46    | ((evacuat\$3 or vacuum\$3) and (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same (electron adj beam or ultraviolet or x adj ray or gamma)) and (wafer or substrate)) not ((airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)))) and (liquid or wet or solution)  | EPO; JPO                       | 2003/08/22<br>08:28 |
| 18 | 41377 | (vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>08:42 |
| 19 | 21350 | (liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))   | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>08:43 |
| 22 | 5998  | ((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)  | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>08:46 |
| 23 | 0     | (airtight or hermetic\$5) and (((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma))  | EPO; JPO                       | 2003/08/22<br>08:47 |
| 26 | 7     | ((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)) and 396/611.ccls.   | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>08:52 |
| 27 | 475   | ((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)) and ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>08:53 |

|    |     |  |                                |                     |
|----|-----|--|--------------------------------|---------------------|
| 28 | 192 | (((liquid or solution) same (wash\$3 or rins\$3 or clean\$3) and ((vacuum\$3 or airtight or hermetic\$5) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) and ((wash\$3 or rins\$3 or clean\$3) or (liquid or solution)) same (electron adj beam or ultraviolet or x adj ray or gamma)) and ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam)) or (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer)) not (((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam) and (ultraviolet or x adj ray or gamma)) and (liquid or solution) same ((wash\$3 or rins\$3 or clean\$3) same (wafer or substrate) same electron adj beam))) or (((wash\$3 or rins\$3 or clean\$3) same (liquid or solution) same electron adj beam) and (wash\$3 or rins\$3 or clean\$3) same (substrate or wafer))) | USPAT;<br>US-PGPUB;<br>DERWENT | 2003/08/22<br>08:53 |
|----|-----|--|--------------------------------|---------------------|